Supplementary Information

Preparation of Ni nanoparticles by liquid-phase reduction to fabricate metal nanoparticle–polyimide composite films

Daiki Fujioka

Department of Applied Chemistry, College of Life Sciences, Ritsumeikan University, 1-1-1 Noji-Higashi, Kusatsu-City, Japan Email: rc007040@ed.ritsumei.ac.jp Tel: +81-77-561-2780

Shingo Ikeda

Electronic Materials Research Division, Osaka Research Institute of Industrial Science and Technology, 1-6-50 Morinomiya, Joto-ku, Osaka 536-8553, Japan Email: ikeda-s@omtri.or.jp TEL: +81-6-6963-8087

Kensuke Akamatsu

Department of Nanobiochemistry, Frontiers of Innovative Research in Science and Technology (FIRST), Konan University, 7-1-20 minatojimaminami, Chuo-ku, Kobe 650-0047, Japan Email: akamatsu@center.konan-u.ac.jp TEL: +81-78-303-1447

Hidemi Nawafune

Department of Nanobiochemistry, Frontiers of Innovative Research in Science and Technology (FIRST), Konan University, 7-1-20 minatojimaminami, Chuo-ku, Kobe 650-0047, Japan Email: nawafune@center.konan-u.ac.jp

Kazuo Kojima

Department of Applied Chemistry, College of Life Sciences, Ritsumeikan University, 1-1-1 Noji-Higashi, Kusatsu-City, Japan Email: kojimaka@sk.ritsumei.ac.jp Tel: +81-77-561-2780

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1. XRD patterns of Ni-NPs/PI films without being annealed at 300 °C for 2 h in a nitrogen atmosphere



Figure S1. XRD patterns of Ni-NPs/PI films without being annealed at 300 °C for 2 h in a nitrogen atmosphere. The films were prepared by immersed polyimide film containing Ni²⁺ ions into KBH₄ aqueous solutions of (A) 0.02, (B) 0.06, (C) 0.12, and (D) 0.20 mol dm⁻³. A polyimide film without embedded nickel ions (PI) shows no nickel diffraction patterns.

2. Cross-sectional TEM image and particle size distributions of a Ni-NPs/PI films reduced at 50 $^{\circ}\mathrm{C}$



Figure S2. Cross-sectional TEM image (left) and particle size distributions (right) of a Ni-NPs/PI films reduced at 50 °C. The film was prepared by immersing Ni²⁺-ions containing polyimide film into KBH₄ aqueous solution of 0.20 mol dm⁻³

 X-ray diffraction patterns of samples subjected repeatedly to adsorption/reduction treatment of Ni²⁺ ions



Figure S3. X-ray diffraction patterns of samples subjected repeatedly to adsorption/reduction treatment of Ni²⁺ ions: (PI) polyimide film without embedded Ni²⁺ ions, and samples repeated Ni²⁺ ion adsorption/reduction treatment for (A) one cycle, and (B) three, (C) five, and (D) seven cycles. The (PI) film shows no nickel diffraction patterns.

4. Cross-sectional TEM images and particle size distributions of samples repeated Ni²⁺ ion adsorption/reduction treatment



Figure S4. Cross-sectional TEM images (left) and particle size distributions (right) of samples repeated Ni²⁺ ion adsorption/reduction treatment for (a) three, (b) five, and (c) seven cycles.

5. Electron diffraction patterns of the samples obtained by repeated Ni²⁺-ion adsorption/reduction treatment



Figure S5. Electron diffraction patterns of the samples obtained by repeated Ni²⁺-ion adsorption/reduction treatment for (b) three, (c) five, and (d) seven cycles. A sample (a) reduced with the 0.20-mol dm⁻³ KBH₄ aqueous solution at 50 °C with one repetition number.

6. Comparison of X-ray diffraction patterns of fcc-Ni and Ni borides



Figure S6. Comparison of X-ray diffraction patterns of fcc-Ni and Ni borides.